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AMENDMENTS TO THE CLAIMS:

Claims 1-12. (Canceled).

Claim 13. (Previously presented) A method for producing a transparent laminate comprising:

- preparing a transparent substrate;
- depositing a high-refractive-index transparent thin film by a vacuum dry process;
- depositing a silver transparent conductive thin film by a vacuum dry process;
- repeating the depositing of the high-refractive-index transparent thin film and the silver transparent conductive thin film at least three times to thereby form at least three combination thin-film layers of the high-refractive-index transparent thin film and the silver transparent conductive thin film successively laminated on a surface of said transparent substrate; and

- depositing another high-refractive-index transparent thin film on a surface of said combination thin-film layer by the vacuum dry process,

- wherein, when said silver transparent conductive thin films are deposited by the vacuum dry process, a temperature T (K) of said transparent substrate at the time of the deposition of said films is set to be in a range $340 \leq T \leq 390$.

Claim 14. (Previously presented) A method for producing a transparent laminate comprising:

- preparing a transparent substrate;
- depositing a high-refractive-index transparent thin film by a vacuum dry process;

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depositing a silver transparent conductive thin film by a vacuum dry process;
repeating forming of the high-refractive-index transparent thin film and the silver transparent conductive thin film at least three times to thereby form at least three combination thin-film layers of the high-refractive-index transparent thin film and the silver transparent conductive thin film successively laminated on a surface of said transparent substrate; and
depositing another high-refractive-index transparent thin film on a surface of said combination thin-film layer by the vacuum dry process,

wherein, when said silver transparent conductive thin films are deposited by the vacuum dry process, a temperature T (K) of said transparent substrate at the time of the deposition of said films is set to be in a range $340 \leq T \leq 390$, and a deposition rate R (nm/sec) of said silver transparent conductive thin films is set to be $R = (1/40) \times (T - 300) \pm 0.5$.

Claim 15. (Previously presented) The method of claim 13, further comprising depositing a low-refractive-index transparent thin film.

Claim 16. (Previously presented) The method of claim 15, wherein the low-refractive-index transparent thin film is deposited before any high-refractive-index thin film is deposited.

Claim 17. (Previously presented) The method of claim 15, wherein the low-refractive-index transparent thin film is deposited after all of the high-refractive-index thin films are deposited.

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Claim 18. (Previously presented) A method of producing a plasma display filter, with the method of claim 13, further comprising disposing said transparent laminate in front of a display portion of a plasma display panel.

Claim 19. (Previously presented) The method of claim 14, further comprising depositing a low-refractive-index transparent thin film.

Claim 20. (Previously presented) The method of claim 19, wherein the low-refractive-index transparent thin film is deposited before any high-refractive-index thin film is deposited.

Claim 21. (Previously presented) The method of claim 19, wherein the low-refractive-index transparent thin film is deposited after all of the high-refractive-index thin films are deposited.

Claim 22. (Previously presented) The method of claim 14, further comprising disposing said transparent laminate in front of a display portion of a plasma display panel.

Claim 23. (Previously presented) The method of claim 13, wherein said vacuum dry process comprises a sputtering process.

Claim 24. (Previously presented) The method of claim 13, wherein said silver transparent conductive thin film comprises silver and 5 % by weight of gold.

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Claim 25. (Previously presented) The method of claim 13, wherein said repeated depositing is repeated only three times to form three combination thin-film layers.

Claim 26. (Previously presented) The method of claim 14, wherein said vacuum dry process comprises a sputtering process.

Claim 27. (Previously presented) The method of claim 14, wherein said silver transparent conductive thin film comprises silver and 5 % by weight of gold.

Claim 28. (Previously presented) The method of claim 14, wherein said repeated depositing is repeated only three times to form three combination thin-film layers.